UNITED STATES PATENT AND TRADEMARK OFFICE ————— BEFORE THE PATENT TRIAL AND APPEAL BOARD ———— TAIWAN SEMICONDUCTOR MANUFACTURING CO., LTD, Petitioner,

v.

GODO KAISHA IP BRIDGE 1, Patent Owner.

Case No. IPR2017-01843¹ Patent 7,893,501

PATENT OWNER'S NOTICE OF FILING TRANSCRIPT OF JULY 19, 2018 CONFERENCE CALL

¹ Case IPR2017-01842 has been consolidated with this proceeding.



Exhibit	Description
2201	Request for Continued Examination dated March 29, 2010
2202	U.S. Patent No. 6,437,404 ("Xiang")
2203	U.S. Patent No. 6,870,230 ("Matsuda")
2204	Office Action dated May 10, 2010
2205	U.S. Patent No. 3,390,022
2206	McGraw-Hill Dictionary of Scientific and Technical Terms (2003)
2207	Declaration of Joshua J. Miller in Support of Motion for Admission <i>Pro</i>
	Hac Vice
2208	Declaration of Alexander D. Glew, Ph.D., P.E.
2209	Transcript of the Deposition of Stanley R. Shanfield, Ph.D. (March 27, 2018)
2210	Transcript of the Deposition of Stanley R. Shanfield, Ph.D. (March 28, 2018)
2211	Exhibit 2001 from March 27-28 Deposition of Dr. Stanley Shanfield, Ph.D., annotated version of '501 Patent
2212	Exhibit 2001 from March 27-28 Deposition of Dr. Stanley Shanfield, Ph.D., annotated version of Igarashi
2213	Exhibit 2003 from March 27-28 Deposition of Dr. Stanley Shanfield, Ph.D., Hawley's Condensed Chemical Dictionary, Twelfth Edition (1993)
2214	Exhibit 2004 from March 27-28 Deposition of Dr. Stanley Shanfield, Ph.D., annotated version of Xiang (Ex. 2202)
2215	Exhibit 2005 from March 27-28 Deposition of Dr. Stanley Shanfield, Ph.D., annotated versions of Fig. 12 of Igarashi
2216	Exhibit 2006 from March 27-28 Deposition of Dr. Stanley Shanfield, Ph.D., annotated versions of Fig. 12 of Igarashi
2217	U.S. Pat. No. 6,924,237
2218	U.S. Pub. No. 2004/0164359
2219	U.S. Pat. No. 4,908,324
2220	U.S. Pat. No. 5,792,695
2221	U.S. Pat. No. 6,020,233
2222	Park, et al., A Study on Modified Silicon Surface after CHF ₃ /C ₂ F ₆
	Reactive Ion Etching, 16 ETRI Journal 45 (1994)
2223	Miyatake, et al., Surface Contamination Control During Plasma
	Etching, 1593 SPIE 47 (1991)
2224	Kastenmeier, et al., Gas Utilization in Remote Plasma Cleaning and
	Stripping Applications, 18(5) J. VAC. SCI. TECH. 2102 (2000)
2225	Butterbaugh, et al., Plasma-Surface Interactions in Fluorocarbon



Exhibit	Description
	Etching of Silicon Dioxide, 9(3) J. VAC. SCI. TECH. 1461 (1991)
2226	Schaepkens, et al., Study of the SiO ₂ -toSi ₃ N ₄ Etch Selectivity
	Mechanism in Inductively Coupled Fluorocarbon Plasmas and a
	Comparison with the SiO ₂ -to-Si Mechanism, 17(1) J. VAC. SCI. TECH.
	26 (1999)
2227	U.S. Patent No. 5,505,816
2228	The American Heritage College Dictionary (Third Edition)
2229	Curriculum vitae of Alexander D. Glew, Ph.D., P.E.
2030	Transcript of July 19, 2018 Conference Call



Pursuant to 37 CFR §42.6(e)(4)(ii), Patent Owner herewith submits a copy of the following Exhibit:

Exhibit	Description
2230	Transcript of July 19, 2018 Conference Call

Dated: July 20, 2018 Respectfully submitted, Godo Kaisha IP Bridge 1

By /s/ Joshua J. Miller
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CERTIFICATE OF SERVICE UNDER 37 C.F.R. §42.6 (e)(4)

I certify that on July 20, 2018 I will cause a copy of the foregoing document, including any exhibits referred to therein, to be served via electronic mail, as previously consented to by Petitioner, upon the following:

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